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PATENT
MIC04 P-106

Official

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Imad Mahawili, Ph.D
Serial No. : 09/488,309
Filing Date : January 20, 2000
Group Art : 1763
For : REACTOR WITH REMOTE PLASMA SYSTEM AND
METHOD OF PROCESSING A SEMICONDUCTOR SUBSTRATE

FAX RECEIVED

JAN 20 2001

GROUP 1700

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

PRELIMINARY AMENDMENT

Prior to examination, Applicant respectfully requests the following
amendments be entered into the case:

IN THE CLAIMS:

Please amend Claims 3, 5, 13, 15, 18, 32, and 36 as follows:

3. (Amended)

A¹ The reactor according to Claim 2, further comprising a heater housing
supported in said reactor housing and enclosing said heater therein[, said heater housing
being adapted to rotatably support the substrate in said processing chamber].

5. (Amended)

A² The reactor according to Claim 4, wherein said plasma generator generates an
electromagnetic field, said electromagnetic field for ionizing the gas into a gas plasma.

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